

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Masaharu Nagai et al. Art Unit : Unknown
Serial No. : New Application Examiner : Unknown
Filed : October 29, 2003
Title : METHOD FOR REMOVING RESIST PATTERN AND METHOD FOR
MANUFACTURING SEMICONDUCTOR DEVICE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

PETITION TO ACCEPT COLOR PHOTOGRAPHS

Applicants hereby petition under 37 CFR §1.84(b)(2) that the color photographs filed in the application be accepted.

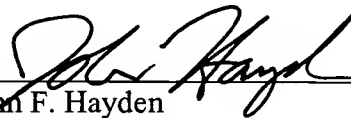
The subject matter of the invention relates to a method for removing a resist pattern that is formed in a photolithography process and a method for manufacturing a semiconductor device by using the method for removing a resist pattern. The color photographs in figures 7A-7H and 8A-8C are necessary to accurately and clearly depict the subject matter sought to be patented.

Enclosed is a check for \$130 to cover the fee required under 37 CFR §1.17(i), three (3) sets of the color photographs, a black and white set of the photographs and an amendment to insert a reference to the color photographs into the specification.

Please apply any other charges or credits to Deposit Account No. 06-1050.

Respectfully submitted,

Date: October 29, 2003



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